

jc978 U.S. PTO
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02/19/02

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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10076630	FILING DATE 02/19/2002	CLASS 438	SUBCLASS	GAU 2812	EXAMINER
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**APPLICANTS: Chung Chia-Chi; Hsueh Chen-Chen;

**CONTINUING DATA VERIFIED:

** FOREIGN APPLICATIONS VERIFIED:

PG-PUB DO NOT PUBLISH ☐

RESCIND ☐

Foreign priority claimed

☐ yes ☐ no

35 USC 119 conditions met

☐ yes ☐ no

Verified and Acknowledged Examiners's initials

ATTORNEY DOCKET NO

8409.0004-00

TITLE : Self-aligned patterning in dual damascene process

U.S. DEPT. OF COMM./PAT. & TM-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED		
			Total Claims	Print Claim for O.G.	
ISSUE FEE		Primary Examiner	DRAWING		
Amount Due	Date Paid		Sheets Drwg.	Figs. Drwg.	Print Fig.
			2	6	3, 4, 5
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE	Application Examiner		
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